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Journal
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PRIORITY PATENT APPLICATION SERIAL NO. 08/696,243
PRIORITY FILING DATE 08/13/96
INVENTORSHIP Schuegraf
PRIORITY GROUP ART UNIT 2813
PRIORITY EXAMINER M. Whipple
ATTORNEY'S DOCKET NO. MI22-1098
TITLE Semiconductor Processing Methods of Chemical Vapor Depositing
SiO₂ on a Substrate

Assistant Commissioner for Patents
Washington, D. C. 20231
Attention: Official Draftsman

SUBSTITUTE DRAWING REQUEST

Please enter the enclosed substitute drawings in the
above-referenced application in place of drawings originally filed. The
content of the drawings are identical to those now on file in this
application.

1 Acknowledgment of receipt of the formal drawings and their
2 acceptance into the file is requested.

Respectfully submitted,

Date:

12/15/98

By:

Lance R. Sadler

Reg. No.: 38,605

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Enclosures: 2 Formal Sheets of Drawings, Figs. 1-4